


U.S. Department of Commerce, Patent and Trademark Office				Docket No.: 6976/Y01/SYNX/SYNX/HMM		Serial No.: 10/650,312	
 <p>LIST OF RELEVANT ART CITED BY APPLICANT (Use several sheets if necessary)</p>				Applicants: Martin R. Elliott et al.			
				Filing Date: August 28, 2003		Group: 3652	
U.S. Patent Documents							
*Examiner Initial		Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
/CG/	US-1	5,372,471	12/13/94	Wu			
	US-2	4,027,246	05/31/77	Caccoma et al.			
	US-3	6,082,948	07/04/00	Fishkin et al.			
	US-4	5,888,042	03/30/99	Oda			
	US-5	6,048,259	04/11/00	Asai			
	US-6	3,845,286	10/29/74	Aronstein et al.			
	US-7	6,026,561	02/22/00	Lafond			
	US-8	5,884,392	03/23/99	Lafond			
	US-9	5,411,358	05/02/95	Garric et al.			
	US-10	5,382,127	01/17/95	Garric et al.			
	US-11	4,166,527	09/04/79	Beezer			
Foreign Patent Documents							
							Translation
		Document Number	Date	Country	Class	Subclass	Yes No
	F-1	JP 08-046005	02/16/96	Japan			X
	F-2	JP 11-121585	04/30/99	Japan			X
	F-3	WO 97/03001 A1	01/30/97	PCT			X
	F-4	WO 98/50946 A1	11/12/98	PCT			X
	F-5	WO 99/28952 A2	06/10/99	PCT			X
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
	OT-1	Weiss, Mitchell, "Evaluating 300-mm Fab Automation Technology Options and Selection Criteria", June 1997, MICRO, Vol. 15, No. 6, pages 65-66, 68, 70, 72, 74, 76, 78-79.					
	OT-2	Ebert, et al., "Efficient CFD Modeling of Single-Wafer Semiconductor Fabrication Systems for Closed-Loop Evaluation", Dec. 1997, Proceedings of the 36th IEEE Conference on Decision and Control, Vol. 1, pages 830-831.					
	OT-3	Kobayashi, et al., "Particle Characteristics of 300-mm Minienvironment (FOUP and LPU)", 1999, Proceedings of 1999 IEEE International Symposium on Semiconductor Manufacturing Conference Proceedings, pages 39-42.					
Examiner	/Charles Greenhut/		Date Considered 03/30/2007				

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

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/CG/	US-12	5,818,716	10/06/98	Chin et al.			
/CG/	US-13	5,612,886	03/18/97	Weng			
/CG/	US-14	5,976,199	11/02/99	Wu et al.			
/CG/	US-15	5,256,204	10/26/93	Wu			
	US-16						
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	US-18						
	US-19						
	US-20						
	US-21						
	US-22						

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		Document Number	Date	Country	Class	Subclass	Yes	No
/CG/	F-6	WO 00/44653 A1	08/03/00	PCT			X	
	F-7	WO 00/59004 A1	10/05/00	PCT			X	
	F-8	WO 01/01828 A1	01/11/01	PCT			X	
	F-9	WO 01/10756 A1	02/15/01	PCT			X	
	F-10	WO 02/04774 A2	01/17/02	PCT			X	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

OT-4	No-Author, "PRI Selected By Varian Semiconductor to Supply 300mm Integrated Front-End Buffering Solutions", Feb. 10, 2000, Newswire, Page 7434.
OT-5	
OT-6	

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	US-24					
	US-25					
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	US-29					
	US-30					
	US-31					
	US-32					
	US-33					

Foreign Patent Documents

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	Document Number	Date	Country	Class	Subclass	Yes	No
/CG/	F-11	EP 0513651 A1	11/19/92	EPO		X	
	F-12	EP 0219826 B1	09/07/94	EPO		X	
	F-13	EP 0472536 B1	12/14/94	EPO		X	
	F-14	EP 0651429 A1	05/03/95	EPO		X	
	F-15	EP 0556193 B1	12/06/95	EPO		X	

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	OT-7	
	OT-8	
	OT-9	

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	US-35						
	US-36						
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	US-38						
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	US-40						
	US-41						
	US-42						
	US-43						
	US-44						

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		Document Number	Date	Country	Class	Subclass	Yes	No
/CG/	F-16	EP 0663686 B1	06/18/97	EPO			X	
↓	F-17	EP 0684631 B1	04/01/98	EPO			X	
	F-18	EP 0555891 B1	01/20/99	EPO			X	
	F-19	EP 0663686 A1	07/19/95	EPO			X	
	F-20	EP 0365589 B1	09/23/92	EPO			X	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	OT-10	
	OT-11	
	OT-12	

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